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	Application No.	Applicant(s)	
	10/762,969	HO ET AL.	
Notice of Allowability	Examiner	Art Unit	
	Lan Vinh	1765	
The MAILING DATE of this communication apperalled in the Mail Claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIPORT of the Office or upon petition by the applicant. See 37 CFR 1.313 1. This communication is responsive to Amendment filed on the Communication is responsive to Amendment filed on the Communication is made of a claim for foreign priority under the Communication is made of a claim for foreign priority under the Communication is made of the priority documents have	ears on the cover sheet with the co (OR REMAINS) CLOSED in this app or other appropriate communication (GHTS. This application is subject to and MPEP 1308.	orrespondence addrolication. If not include will be mailed in due	ed course. THIS
 Certified copies of the priority documents have Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received:	been received in Application Nocuments have been received in this r	national stage applica	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	ENT of this application.		
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give	itted. Note the attached EXAMINER' es reason(s) why the oath or declarat	S AMENDMENT or Nation is deficient.	OTICE OF
 CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1) each sheet. Replacement sheet(s) should be labeled as such in the 	on's Patent Drawing Review (PTO-S s Amendment / Comment or in the O .84(c)) should be written on the drawin	ffice action of	e back) of
6. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT	sit of BIOLOGICAL MATERIAL m FOR THE DEPOSIT OF BIOLOGICA	nust be submitted. N AL MATERIAL.	Note the
Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	5. ☐ Notice of Informal Pa 6. ☐ Interview Summary Paper No./Mail Date 8), 7. ☒ Examiner's Amendm 8. ☒ Examiner's Stateme 9. ☐ Other	(PTO-413), e nent/Comment	
		Lan Vinh AU 1765	

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EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

In page 1 of the specification, "This application is a DIV of 09/782,446 filed on 2/12/2001, now US Patent 6,893,969" has been inserted below the headline of RELATED APPLICATION

On line 8 in page 1 of the specification, "09/782,185" has been inserted after "Application No:"

On line 13 in page 1 of the specification, "09/782,678" has been inserted after "Application No:"

On line 19 in page 1 of the specification, "09/782,437" has been inserted after "Application No:"

Allowable Subject Matter

2. Claims 17-18, 22, 24-31, 33-39 allowed

The following is a statement of reasons for allowance:

Regarding claim 17, the cited prior art of record fails to disclose or suggest an integrated circuit formed from the step of "placing an etch stop....; placing a second

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organic dielectrichardmask.", in combination with the rest of the limitations of claim

Regarding claim 31, the cited prior art of record fails to disclose or suggest an integrated circuit formed from the method comprises the step of "providing CHF3 while providing the etching gas comprising NH3", in combination with the rest of the limitations of claim 31

Regarding claim 37, the cited prior art of record fails to disclose or suggest an integrated circuit formed from the method comprises the step of "etching features into the organic dielectric layer using the plasma from the NH3", in combination with the rest of the limitations of claims 37, 39

Conclusion

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lan Vinh whose telephone number is 571 272 1471. The examiner can normally be reached on M-F 8:30-5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571 272 1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

June 19, 2006